Please amend the paragraph beginning at page 4, line 24 of the specification as follows:

Commonly assigned, co-pending U.S. patent application Serial No. 10/082,178, filed February 26, 2002 ~~(Attorney Docket No. 50103-401)~~, the entire disclosure of which is incorporated herein by reference, discloses an improvement over the invention disclosed in commonly assigned U.S. Pat. 5,991,104, and is based upon the finding that very sharply defined magnetic transition patterns can be reliably, rapidly, and cost-effectively formed in a magnetic medium containing a longitudinal or perpendicular type magnetic recording layer without requiring expensive, complicated fabrication of a master disk.

Please amend the paragraph beginning at page 8, line 10 of the specification as follows:

Referring now to FIG. 5, schematically illustrated therein, in simplified cross-sectional view, is a sequence of processing steps for performing nano-imprint lithography of a metal-based workpiece, e.g., a disk-shaped substrate for a hard disk recording medium, utilizing a stamper/imprinter with a lubricated imprinting surface, as disclosed in commonly assigned, co-pending U.S. patent application Serial No. 09/946,939, filed September 5, 2001 ~~(Attorney Docket No. 50103-381)~~, the entire disclosure of which is incorporated herein by reference.

Please amend the paragraph beginning at page 9, line 7 of the specification as follows:

Still another process which has been recently studied and developed as a low cost alternative technique for fine dimension pattern/feature formation in a substrate surface is imprinting of a sol-gel layer on a substrate surface, as for example, disclosed in commonly assigned, co-pending U.S. patent application Serial No. 09/852,084, filed May 10, 2001 ~~(Attorney Docket No. 50103-377)~~, the entire disclosure of which is incorporated herein by reference.